

SPECIFICATION

ADHESIVE FILM, MULTILAYER CIRCUIT BOARD, ELECTRONIC
COMPONENT AND SEMICONDUCTOR DEVICE

5

TECHNICAL FIELD

[0001]

The present invention relates to an adhesive film, a multilayer circuit board, an electronic component and a semiconductor device.

10

BACKGROUND ART

[0002]

With the recent requirements of higher functionality, lightness, thinning, miniaturization and compactization in electronic equipments, high-density integration and high-density mounting of electronic components such as semiconductor packages and the like are in progress, while reduction in size and high pin counts of these electronic components are in progress. In order to achieve electrical connection of these electronic components, solder bonding is used.

15

20

[0003]

As solder bonding, there may be, for example, a conductive bonding portion between semiconductor chips, a conductive bonding portion between a semiconductor chip and a circuit board such as a package with a flip chip

25

mounting, a conductive bonding portion between circuit boards, and the like. In order to secure the electrical connection strength and mechanical connection strength, an encapsulating resin which is generally called an
5 underfill material is injected into this solder bonding portion (underfill encapsulation).

[0004]

When gaps generated in this solder bonding portion are reinforced with a liquid encapsulating resin (an underfill
10 material), the liquid encapsulating resin (the underfill material) is supplied after solder bonding and the resultant is cured, whereby the solder bonding portion is reinforced. However, with thinning and reduction in size of the electronic components, the solder bonding portion
15 has narrow pitches and narrow gaps, so that although the liquid encapsulating resin (the underfill material) is supplied after solder bonding, there is a problem such that the liquid encapsulating resin (the underfill material) is not spread between gaps and not fully filled
20 therebetween either.

[0005]

In response to such a problem, there has been known a method involving carrying out electrical connection and attachment between terminals at one time through an
25 anisotropic conductive film. For example, there have been disclosed a method in which an adhesive film containing solder particles is interposed between members and the

resultant is subjected to thermo-compression bonding, whereby solder particles are interposed between terminals of both members and a resin component is filled in the other portion, and a method of achieving electrical connection
5 by the contact with metal particles (for example, see Patent Documents 1 and 2).

RELATED DOCUMENT

PATENT DOCUMENT

10 [0006]

Patent Document 1: Japanese Unexamined Patent
Application Publication No. S61-276873

Patent Document 2: Japanese Unexamined Patent
Application Publication No. H09-31419

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DISCLOSURE OF THE INVENTION

[0007]

However, in these methods, it was difficult to secure insulation properties between adjacent terminals because
20 of the presence of conductive particles between adjacent terminals, and difficult to secure the reliability of the electronic component and the semiconductor device because of the presence of bubbles between adjacent terminals.

[0008]

25 An object of the present invention is to provide an adhesive film which can achieve both excellent electrical connectivity and insulation reliability while connecting

between terminals of opposing members and encapsulating gaps between members, and a multilayer circuit board, an electronic component and a semiconductor device using the adhesive film.

5 [0009]

Such an object is achieved by the matters described in the following [1] to [14].

[0010]

[1] An adhesive film electrically connecting a first
10 terminal of a support and a second terminal of an adherend using solders, and attaching the support to the adherend, wherein the adhesive film contains a thermosetting resin (A), a curing agent (B), a compound having flux activity (C) and a film forming resin (D), the minimum melt
15 viscosity of the adhesive film is from 0.01 to 10,000 Pa·s, and the adhesive film satisfies the following formula (1) when the exothermic peak temperature (degrees centigrade) of the adhesive film is defined as (a) and the 5% weight loss temperature by thermogravimetry (degrees centigrade)
20 of the adhesive film is defined as (b),

$$(b)-(a) \geq 100 \text{ degrees centigrade} \quad (1).$$

[2] The adhesive film according to [1], wherein the mixing ratio ((A)/(C)) of the thermosetting resin (A) to the compound having flux activity (C) is from 0.5 to 20.

25 [0011]

[3] The adhesive film according to [1] or [2], wherein the content of the thermosetting resin (A) is from 5 to

80% by weight, based on the adhesive film.

[4] The adhesive film according to any one of [1] to [3], wherein the thermosetting resin (A) is an epoxy resin.

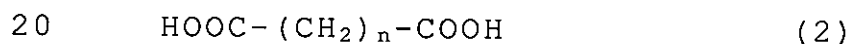
[0012]

5 [5] The adhesive film according to any one of [1] to [4], wherein the compound having flux activity (C) is a flux activating compound having a carboxyl group and/or a phenolic hydroxyl group.

10 [6] The adhesive film according to any one of [1] to [4], wherein the compound having flux activity (C) is a flux activating compound containing, in one molecule thereof, two phenolic hydroxyl groups and at least one carboxyl group which is directly bonded to an aromatic ring.

15 [0013]

[7] The adhesive film according to any one of [1] to [6], wherein the compound having flux activity (C) contains a compound represented by the following general formula (2),



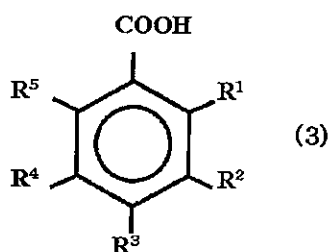
wherein, in the general formula (2), n is an integer of 1 to 20.

[0014]

25 [8] The adhesive film according to any one of [1] to [6], wherein the compound having flux activity (C) contains a compound represented by the following general formula (3) and/or (4),

[0015]

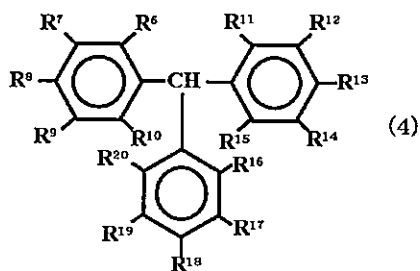
[Chemical Formula 1]



wherein, in the general formula (3), R^1 to R^5 are each independently a monovalent organic group, and at least one of R^1 to R^5 is a hydroxyl group,

[0016]

[Chemical Formula 2]



wherein, in the general formula (4), R^6 to R^{20} are each independently a monovalent organic group, and at least one of R^6 to R^{20} is a hydroxyl group or a carboxyl group.

[0017]

[9] The adhesive film according to any one of [1] to [8], wherein the adhesive film further contains a filler (G).

[10] The adhesive film according to [9], wherein the content of the filler (G) is equal to or more than 0.1% by weight and equal to or less than 80% by weight, based on the adhesive film.

[0018]

[11] The adhesive film according to any one of [1] to [10], wherein the adhesive film further contains a silane coupling agent (F) in an amount of equal to or more than 5 0.01% by weight and equal to or less than 5% by weight, based on the adhesive film.

[12] A multilayer circuit board, having a cured product of the adhesive film according to any one of [1] to [11].

[0019]

10 [13] An electronic component, having a cured product of the adhesive film according to any one of [1] to [11].

[14] A semiconductor device, having a cured product of the adhesive film according to any one of [1] to [11].

15 EFFECT OF THE INVENTION

[0020]

According to the present invention, there are provided an adhesive film which can achieve both excellent electrical connectivity and insulation reliability while 20 connecting between terminals of opposing members and encapsulating gaps between members, and a multilayer circuit board, an electronic component and a semiconductor device using the adhesive film.

25 BRIEF DESCRIPTION OF THE DRAWINGS

[0021]

Fig. 1 is a process cross-sectional view illustrating

one example of the method for producing a semiconductor device using the adhesive film of the present invention.

DESCRIPTION OF EMBODIMENTS

5 [0022]

Hereinafter, the adhesive film, the multilayer circuit board, the electronic component and the semiconductor device of the present invention will be described.

[0023]

10 The adhesive film of the present invention is an adhesive film electrically connecting a first terminal of a support and a second terminal of an adherend using solders, and attaching the support to the adherend, in which the adhesive film contains a thermosetting resin (A),
15 a curing agent (B), a compound having flux activity (C) and a film forming resin (D), the minimum melt viscosity of the adhesive film is from 0.01 to 10,000 Pa·s, and the adhesive film satisfies the following formula (1) when the exothermic peak temperature (degrees centigrade) of the
20 adhesive film is defined as (a) and the 5% weight loss temperature by thermogravimetry (degrees centigrade) of the adhesive film is defined as (b),

$$(b)-(a) \geq 100 \text{ degrees centigrade} \quad (1)$$

[0024]

25 Furthermore, the multilayer circuit board, the electronic component and the semiconductor device of the present invention are obtained by electrically connecting

a support having a first terminal and an adherend having a second terminal and attaching the support to the adherend by the use of the aforementioned adhesive film.

[0025]

5 Hereinafter, the adhesive film, the multilayer circuit board, the electronic component and the semiconductor device of the present invention will be described in detail.

[0026]

10 Adhesive Film

The minimum melt viscosity of the adhesive film of the present invention is from 0.01 to 10,000 Pa·s. When the minimum melt viscosity of the adhesive film is from 0.01 to 10,000 Pa·s, excellent connection reliability can be
15 secured at the time that the adhesive film is interposed between the first terminal of the support and the second terminal of the adherend facing to each other, the adhesive film is heated and melted, and the support and the adherend are electrically connected to each other and attached.

20 [0027]

When the minimum melt viscosity is equal to or more than 0.01 Pa·s, it is possible to prevent the melted adhesive film from being crept into the support and the adherend, and from contaminating the support and the adherend. On
25 the other hand, when the minimum melt viscosity is equal to or less than 10,000 Pa·s, it is possible to prevent the melted adhesive film from being caught between opposing

terminals and from causing conduction defects.

[0028]

The minimum melt viscosity is preferably equal to or more than 0.02 Pa·s and particularly preferably equal to
5 or more than 0.05 Pa·s. Thus, it is possible to more effectively prevent the melted adhesive film from being crept into the support and the adherend, and from contaminating the support and the adherend. On the other hand, the minimum melt viscosity is preferably equal to
10 or less than 8,000 Pa·s and particularly preferably equal to or less than 7,000 Pa·s. Thus, it is possible to more effectively prevent the melted adhesive film from being caught between opposing terminals and from causing conduction defects.

15 [0029]

Herein, the minimum melt viscosity of the adhesive film may be measured under the conditions of a parallel plate of 20 mmφ, a gap of 0.05 mm, a frequency of 0.1 Hz and a temperature increase rate of 10 degrees centigrade/min
20 using a viscoelasticity measuring instrument (RheoStress RS150, commercially available from HAKKE Corp.).

[0030]

A method of having the melt viscosity of the adhesive film in the above range is not particularly limited, but
25 it may be carried out by properly selecting the softening points and the mixing amounts of the thermosetting resin (A), the curing agent (B) and the film forming resin (D)

constituting the adhesive film.

[0031]

Meanwhile, the adhesive film satisfies the following formula (1) when the exothermic peak temperature of the adhesive film is defined as (a) and the 5% weight loss temperature by thermogravimetry of the adhesive film is defined as (b). Thus, generation of voids can be inhibited at the time that the adhesive film is interposed between the first terminal of the support body and the second terminal of the adherend facing to each other, the adhesive film is heated and melted, and the support body and the adherend are electrically connected to each other and attached. Thus, it is possible to improve the reliability of the multilayer circuit board, the electronic component and the semiconductor device that are manufactured.

$$(b)-(a) \geq 100 \text{ degrees centigrade (1)}$$

[0032]

In the present invention, the exothermic peak temperature (a) refers to one of physical properties exhibiting curing behavior of an adhesive film. When the exothermic peak temperature (a) is low, a curing reaction easily takes place, so that the contact between the electrodes is inhibited or life (storage stability) is reduced in some cases. On the contrary, when the exothermic peak temperature (a) is excessively high, there is a problem of an increase in the heating temperature for curing.

[0033]

On the other hand, in the present invention, the 5% weight loss temperature by thermogravimetry (b) refers to one of physical properties exhibiting heat resistance of an adhesive film. As the 5% weight loss temperature by thermogravimetry (b) is increased, heat resistance will be preferably increased. Furthermore, the 5% weight loss temperature by thermogravimetry (b) being low means that there are lots of decomposition products and volatile substances due to heating. That is, as the 5% weight loss temperature by thermogravimetry (b) is lowered, causes of voids (bubbles) will be increased in the adhesive film after curing and voids will be easily caused.

[0034]

When the difference between the 5% weight loss temperature by thermogravimetry (b) and the exothermic peak temperature (a) of the adhesive film is equal to or more than 100 degrees centigrade, the support and the adherend are electrically connected by heating and melting the adhesive film so as not to proceed with the curing reaction of the adhesive film that much, and thereafter the support and the adherend are attached to each other by heating and curing the adhesive film. Furthermore, when it is equal to or more than 100 degrees centigrade, margin in a process is secured, and occurrence of voids is much reduced.

[0035]

Accordingly, as the difference between the 5% weight loss temperature by thermogravimetry (b) and the exothermic peak temperature (a) of the adhesive film is increased, outgases will be hardly generated by heating the adhesive film, so that generation of bubbles after electrical connection and attachment can be prevented. Furthermore, even when outgases are generated, the temperature at which outgases begin to be generated is higher than the temperature at which the curing reaction of the adhesive film begins, and outgases are generated after curing of the adhesive film proceeds, so that outgases hardly move in the three-dimensional cross-linked adhesive film. Thus, generation of voids after electrical connection and attachment can be inhibited.

[0036]

The difference between the 5% weight loss temperature by thermogravimetry (b) and the exothermic peak temperature (a) of the adhesive film is preferably equal to or more than 120 degrees centigrade and particularly preferably equal to or more than 150 degrees centigrade. Thus, generation of outgases in the adhesive film can be more effectively inhibited. Furthermore, even if the outgases are temporarily generated, outgases hardly move in the adhesive film, so that generation of voids after electrical connection and attachment can be more effectively inhibited.

[0037]

Herein, the exothermic peak temperature (a) of the adhesive film may be measured under the condition of a temperature increase rate of 10 degrees centigrade/min using a differential scanning calorimeter (DSC-6200, commercially available from Seiko Instruments Inc.).

[0038]

The 5% weight loss temperature by thermogravimetry (b) of the adhesive film may be measured under the condition of a temperature increase rate of 10 degrees centigrade/min using a thermo-gravimetric/differential thermal analyzer (TG/DTA6200, commercially available from Seiko Instruments Inc.).

[0039]

A method of having the difference between the 5% weight loss temperature by thermogravimetry (b) and the exothermic peak temperature (a) of the adhesive film in the above range is not particularly limited, but it may be carried out by properly selecting the softening points and the contents of the thermosetting resin (A), the curing agent (B) and the compound having flux activity (C), and further the content of the low molecular weight component.

[0040]

The adhesive film of the present invention contains the thermosetting resin (A), the curing agent (B), the compound having flux activity (C) and the film forming resin (D). Hereinafter, respective components will be

described.

[0041]

(A) Thermosetting Resin

The thermosetting resin (A) is not particularly limited,
5 and examples include an epoxy resin, a phenoxy resin, a
silicone resin, an oxetane resin, a phenol resin, a
(meth)acrylate resin, a polyester resin (an unsaturated
polyester resin), a diallyl phthalate resin, a maleimide
resin, a polyimide resin (a polyimide precursor resin),
10 a bismaleimide-triazine resin and the like. In particular,
preferably used are thermosetting resins containing at
least one kind selected from the group consisting of an
epoxy resin, a (meth)acrylate resin, a phenoxy resin, a
polyester resin, a polyimide resin, a silicone resin, a
15 maleimide resin and a bismaleimide-triazine resin. Among
these, preferably used is an epoxy resin from the
viewpoints of excellent curability, storage stability,
heat resistance of the cured product, moisture resistance
and chemical resistance. Furthermore, these
20 thermosetting resins may be used singly or may be used in
combination of two or more kinds.

[0042]

The content of the thermosetting resin (A) is not
particularly limited, but it is preferably from 5 to 80%
25 by weight, more preferably from 9 to 75% by weight and
particularly preferably from 10 to 55% by weight, based
on the adhesive film. When the content of the

thermosetting resin (A) is equal to or more than the above lower limit, heat resistance of the adhesive film after curing is improved, so that the reliability of the multilayer circuit board, the electronic component and the semiconductor device can be improved. On the other hand, when it is equal to or less than the above upper limit, an excessive increase in the elastic modulus of the adhesive film after curing is inhibited, so that adhesion between the support and the adherend can be improved.

10 [0043]

The aforementioned epoxy resin is not particularly limited and examples include a bisphenol A type epoxy resin, a bisphenol F type epoxy resin, a phenol novolac type epoxy resin, a cresol novolac type epoxy resin, a glycidyl amine type epoxy resin, a glycidyl ester type epoxy resin, a trifunctional epoxy resin, a tetrafunctional epoxy resin and the like.

[0044]

For the aforementioned epoxy resin, the viscosity at 20 25 degrees centigrade is preferably from 500 to 50,000 mPa·s and more preferably from 800 to 40,000 mPa·s. When the viscosity at 25 degrees centigrade is equal to or more than the above lower limit, flexibility and bendability of the adhesive film can be secured. On the other hand, 25 when the viscosity at 25 degrees centigrade is equal to or less than the above upper limit, it is possible to prevent deterioration of handling properties by strong

tack properties of the adhesive film.

[0045]

The content of the aforementioned epoxy resin is not particularly limited, but it is preferably from 5 to 80%
5 by weight and particularly preferably from 9 to 75% by weight, based on the adhesive film. When it is equal to or more than the above lower limit, flexibility and bendability of the adhesive film can be more effectively exhibited. On the other hand, when it is equal to or less
10 than the above upper limit, it is possible to more effectively prevent deterioration of handling properties by strong tack properties of the adhesive film.

[0046]

Among the aforementioned epoxy resins, preferably used
15 are a liquid bisphenol A type epoxy resin and a liquid bisphenol F type epoxy resin from the viewpoint that both control of the melt viscosity of the adhesive film in the range of 0.01 to 10,000 Pa·s and workability (tack properties and bendability) of the adhesive film may be
20 combined.

[0047]

(B) Curing Agent

The curing agent (B) is not particularly limited, and may be properly selected depending on the kind of the
25 thermosetting resin (A) in use. Examples of the curing agent (B) include phenols, amines, thiols, acid anhydrides, isocyanates and the like. These curing agents may be used

singly or may be used in combination of two or more kinds.

[0048]

When an epoxy resin is used as the thermosetting resin (A), phenols are preferably used as the curing agent (B).

5 With the use of phenols as the curing agent (B), heat resistance of the adhesive film after curing is increased and further the moisture absorption ratio is lowered, so that the reliability of the multilayer circuit board, the electronic component and the semiconductor device can be
10 improved.

[0049]

The aforementioned phenols are not particularly limited, and examples include a phenol novolac resin, a cresol novolac resin, a bisphenol A type novolac resin, a
15 bisphenol F type novolac resin, a bisphenol AF type novolac resin and the like. However, preferably used are a phenol novolac resin and a cresol novolac resin in which the glass transition temperature of the cured product of the adhesive film may be effectively increased and components
20 generating outgases may be reduced.

[0050]

The total content of from mononuclear components to trinuclear components in the aforementioned phenol novolac resin or cresol novolac resin is preferably from
25 30 to 70%. Thus, it is possible to increase the glass transition temperature of the cured product of the adhesive film, to decrease the amount of the phenol type

novolac resin generating outgases, and to improve ionic migration resistance. Furthermore, suitable flexibility may be imparted to the adhesive film, so that brittleness of the adhesive film can be improved. Furthermore,

5 suitable tack properties may be imparted to the adhesive film, so that an adhesive film excellent in workability can be obtained.

[0051]

When the total content of from mononuclear components
10 to trinuclear components is smaller than 30% (the total content of tetra- or higher nuclear components is equal to or more than 70%), the reactivity with the aforementioned epoxy resin is lowered and the unreacted phenol type novolac resin in the cured product of the
15 adhesive film remains, so that there are problems such that migration resistance is lowered, the adhesive film becomes brittle, and workability is lowered. On the other hand, when the total content of from mononuclear components to trinuclear components is greater than 70% (the total
20 content of tetra- or higher nuclear components is equal to or less than 30%), there are problems such that the amount of outgases is increased at the time of curing of the adhesive film, thus causing contamination on the surface of the support or the adherend, or deterioration
25 of migration resistance, and tack properties of the adhesive film are increased, thus lowering workability of the adhesive film.

[0052]

The total content of binuclear components and trinuclear components in the aforementioned phenol novolac resin or cresol novolac resin is not particularly limited, but it is preferably from 30 to 70%. When it is equal to or more than the above lower limit, it is possible to more effectively prevent an increase in the amount of outgases at the time of curing of the adhesive film which causes contamination on the surface of the support body or the adherend. On the other hand, when it is equal to or less than the above upper limit, it is possible to more effectively secure flexibility and bendability of the adhesive film.

[0053]

The content of mononuclear components in the aforementioned phenol novolac resin or cresol novolac resin is not particularly limited, but it is preferably equal to or less than 1% and particularly preferably equal to or less than 0.8%, based on the adhesive film. When the content of the mononuclear components is in the above range, the amount of outgases at the time of curing of the adhesive film can be reduced, contamination of the support or the adherend can be suppressed, and further migration resistance can be improved.

[0054]

The weight average molecular weight of the aforementioned phenol novolac resin or cresol novolac

resin is not particularly limited, but it is preferably from 300 to 3,000 and particularly preferably from 400 to 2,800. When it is equal to or more than the above lower limit, it is possible to more effectively prevent an
5 increase in the amount of outgases at the time of curing of the adhesive film which causes contamination on the surface of the support or the adherend. On the other hand, when it is equal to or less than the above upper limit, it is possible to more effectively secure flexibility and
10 bendability of the adhesive film.

[0055]

(C) Compound having flux activity

The adhesive film of the present invention contains a compound having flux activity (C). Thus, an oxide layer
15 formed on the solder surface of at least one of the first terminal of the support and the second terminal of the adherend can be removed, and depending on the situation, an oxide layer formed on the surface of the first terminal of the support or the second terminal of the adherend can
20 be removed, and the first terminal and the second terminal can be surely solder-bonded. Accordingly, it is possible to obtain a multilayer circuit board, an electronic component and a semiconductor device having high connection reliability.

25 [0056]

The compound having flux activity (C) is not particularly limited as long as a flux activating compound

acts to remove the oxide layer on the solder surface, and preferably used is a compound having any of a carboxyl group or a phenolic hydroxyl group, or both of a carboxyl group and a phenolic hydroxyl group.

5 [0057]

The mixing amount of the compound having flux activity (C) is from 1 to 30% by weight and particularly preferably from 3 to 20% by weight. When the mixing amount of the compound having flux activity (C) is in the above range,
10 the flux activity can be improved, and at the same time the unreacted thermosetting resin (A) and compound having flux activity (C) remained at the time of curing of the adhesive film for generating outgases during thermal curing of the adhesive film can be inhibited, and migration
15 resistance can be improved.

[0058]

Meanwhile, the compound having flux activity (C) is present in the compound acting as a curing agent of the epoxy resin (hereinafter such a compound is also referred
20 to as the curing agent having flux activity). For example, an aliphatic dicarboxylic acid, an aromatic dicarboxylic acid and the like acting as a curing agent of the epoxy resin have a flux activity as well. In the present invention, such a curing agent having flux activity acting
25 as a flux and acting as a curing agent of the epoxy resin as well may be suitably used.

[0059]

Incidentally, the compound having flux activity (C) having a carboxyl group refers to a compound having one or more of carboxyl groups in a molecule. Such compounds may be in the form of a liquid or a solid at a room temperature. Meanwhile, the compound having flux activity (C) having a phenolic hydroxyl group refers to a compound having one or more of phenolic hydroxyl groups in a molecule. Such compounds may be in the form of a liquid or a solid at a room temperature. The compound having flux activity (C) having a carboxyl group and a phenolic hydroxyl group refers to a compound having one or more of carboxyl groups and one or more of phenolic hydroxyl groups in a molecule. Such compounds may be in the form of a liquid or a solid at a room temperature.

[0060]

Among these, examples of the compound having flux activity (C) having a carboxyl group include an aliphatic acid anhydride, an alicyclic acid anhydride, an aromatic acid anhydride, an aliphatic carboxylic acid, an aromatic carboxylic acid and the like.

[0061]

Examples of the aliphatic acid anhydride of the compound having flux activity (C) having a carboxyl group include a succinic acid anhydride, a polyadipic acid anhydride, a polyazelaic acid anhydride, a polysebacic acid anhydride and the like.

[0062]

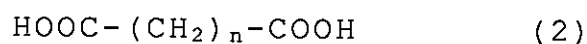
Examples of the alicyclic acid anhydride of the compound having flux activity (C) having a carboxyl group include a methyl tetrahydrophthalic acid anhydride, a methyl hexahydrophthalic acid anhydride, a methyl himic acid anhydride, a hexahydrophthalic acid anhydride, a tetrahydrophthalic acid anhydride, a trialkyl tetrahydrophthalic acid anhydride, a methyl cyclohexene dicarboxylic acid anhydride and the like.

[0063]

Examples of the aromatic acid anhydride of the compound having flux activity (C) having a carboxyl group include a phthalic acid anhydride, a trimellitic acid anhydride, a pyromellitic acid anhydride, a benzophenone tetracarboxylic acid anhydride, ethylene glycol bistrimellitate, glycerol tristrimellitate and the like.

[0064]

Examples of the aliphatic carboxylic acid of the compound having flux activity (C) having a carboxyl group include a compound represented by the following general formula (2), formic acid, acetic acid, propionic acid, butyric acid, valeric acid, pivalic acid, caproic acid, caprylic acid, lauric acid, myristic acid, palmitic acid, stearic acid, acrylic acid, methacrylic acid, crotonic acid, oleic acid, fumaric acid, maleic acid, oxalic acid, malonic acid, succinic acid and the like,



wherein, in the general formula (2), n represents an

integer of equal to or more than 1 and equal to or less than 20.

[0065]

Among the aforementioned aliphatic carboxylic acids, preferably used is a compound represented by the general formula (2) from the viewpoint of an excellent balance among the activity degree of the compound having flux activity (C), the amount of outgases generated at the time of curing of the adhesive film, the elastic modulus and the glass transition temperature of the adhesive film after curing, and the like. Among the compounds represented by the general formula (2), particularly preferably used is a compound in which n is 3 to 10 from the viewpoints that an increase in the elastic modulus in the adhesive film after curing may be suppressed and at the same time adhesion between the support and the adherend may be improved.

[0066]

Among the compounds represented by the general formula (2), examples of the compound in which n is 3 to 10 include glutaric acid ($n=3$: $\text{HOOC}-(\text{CH}_2)_3-\text{COOH}$), adipic acid ($n=4$: $\text{HOOC}-(\text{CH}_2)_4-\text{COOH}$), pimelic acid ($n=5$: $\text{HOOC}-(\text{CH}_2)_5-\text{COOH}$), sebacic acid ($n=8$: $\text{HOOC}-(\text{CH}_2)_8-\text{COOH}$), $\text{HOOC}-(\text{CH}_2)_{10}-\text{COOH}$ ($n=10$) and the like.

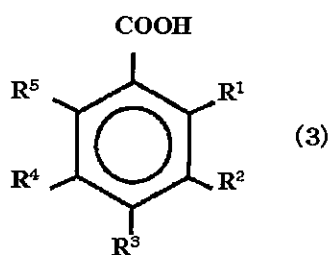
[0067]

Examples of the aromatic carboxylic acid of the compound having flux activity (C) having a carboxyl group include

compounds having flux activity (C) represented by the following general formula (3) or (4),

[0068]

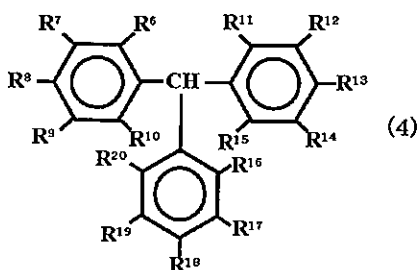
[Chemical Formula 3]



wherein, in the general formula (3), R^1 to R^5 are each independently a monovalent organic group, and at least one of R^1 to R^5 is a hydroxyl group,

[0069]

[Chemical Formula 4]



wherein, in the general formula (4), R^6 to R^{20} are each independently a monovalent organic group, and at least one of R^6 to R^{20} is a hydroxyl group or a carboxyl group.

[0070]

Examples of the aforementioned aromatic carboxylic acid include benzoic acid, phthalic acid, isophthalic acid, terephthalic acid, hemimellitic acid, trimellitic acid, trimesic acid, mellophanic acid, prehnitic acid, pyromellitic acid, mellitic acid, triilic acid, xylic acid,

hemelitic acid, mesitylenic acid, prehnitylic acid,
toluic acid, cinnamic acid, salicylic acid,
2,3-dihydroxybenzoic acid, 2,4-dihydroxybenzoic acid,
gentisic acid (2,5-dihydroxybenzoic acid),
5 2,6-dihydroxybenzoic acid, 3,5-dihydroxybenzoic acid,
gallic acid (3,4,5-trihydroxybenzoic acid), naphthoic
acid derivatives such as 1,4-dihydroxy-2-naphthoic acid
and 3,5-dihydroxy-2-naphthoic acid, phenolphthalin,
diphenolic acid, and the like.

10 [0071]

Among the compounds having flux activity (C)
represented by the general formula (3) or (4), preferably
used is a compound containing, in one molecule thereof,
two or more phenolic hydroxyl groups which may be added
15 to the epoxy resin, and at least one carboxyl group which
is directly bonded to an aromatic ring capable of
exhibiting a flux activity (reduction) from the viewpoint
of improvement in formation of a three-dimensional
cross-linked network of the epoxy resin after curing.
20 Examples of such a curing agent having flux activity
include benzoic acid derivatives such as
2,3-dihydroxybenzoic acid, 2,4-dihydroxybenzoic acid,
gentisic acid (2,5-dihydroxybenzoic acid),
2,6-dihydroxybenzoic acid, 3,4-dihydroxybenzoic acid,
25 gallic acid (3,4,5-trihydroxybenzoic acid) and the like;
naphthoic acid derivatives such as
1,4-dihydroxy-2-naphthoic acid,

3,5-dihydroxy-2-naphthoic acid,
3,7-dihydroxy-2-naphthoic acid and the like;
phenolphthalin; diphenolic acid, and the like. These may
be used singly or may be used in combination of two or more
5 kinds. Among these, preferably used are
2,3-dihydroxybenzoic acid, gentisic acid and
phenolphthalin, which are excellent in the effect of
removing the oxide layer formed on the solder surface and
excellent in the reactivity with the epoxy resin.

10 [0072]

Examples of the compound having flux activity (C) having
a phenolic hydroxyl group include phenols. Concrete
examples include monomers having a phenolic hydroxyl group
such as phenol, o-cresol, 2,6-xyleneol, p-cresol, m-cresol,
15 o-ethylphenol, 2,4-xyleneol, 2,5-xyleneol, m-ethylphenol,
2,3-xyleneol, meditol, 3,5-xyleneol, p-tert-butylphenol,
catechol, p-tert-amylphenol, resorcinol, p-octylphenol,
p-phenylphenol, bisphenol A, bisphenol F, bisphenol AF,
biphenol, diallyl bisphenol F, diallyl bisphenol A,
20 trisphenol, tetrakisphenol and the like.

[0073]

Meanwhile, the mixing amount of the curing agent having
flux activity in the adhesive film is preferably from 1
to 30% by weight and particularly preferably from 3 to 20%
25 by weight. When the mixing amount of the curing agent
having flux activity in the adhesive film is in the above
range, the flux activity of the adhesive film is improved,

and at the same time the epoxy resin and the unreacted curing agent having flux activity are prevented from being remained in the adhesive film. Incidentally, when the unreacted curing agent having flux activity remains,
5 migration takes place.

[0074]

The mixing ratio $((A)/(C))$ of the thermosetting resin (A) to the compound having flux activity (C) is not particularly limited, but it is preferably from 0.5 to 20,
10 particularly preferably from 1 to 18 and further preferably from 2 to 15. When $((A)/(C))$ is equal to or more than the above lower limit, the amount of the compound having flux activity (C) generating outgases is reduced at the time of curing of the adhesive film, so that voids
15 in the adhesive film can be reduced. On the other hand, when $((A)/(C))$ is equal to or less than the above upper limit, the oxide layer formed on the terminal surface of the adherend or the support, or on the solder surface can be effectively removed.

20 [0075]

(D) Film Forming Resin

The adhesive film of the present invention contains a film forming resin (D). Thus, film-forming properties of the adhesive film are improved and make it easy to form
25 a film. Furthermore, mechanical properties of the adhesive film are also excellent.

[0076]

The film forming resin (D) is not particularly limited, and examples include a (meth)acrylic resin, a phenoxy resin, a polyester resin, a polyurethane resin, a polyimide resin, a siloxane-modified polyimide resin, polybutadiene, polypropylene, a styrene-butadiene-styrene copolymer, a styrene-ethylene-butylene-styrene copolymer, a polyacetal resin, a polyvinyl butyral resin, a polyvinyl acetal resin, a butyl rubber, a chloroprene rubber, a polyamide resin, an acrylonitrile-butadiene copolymer, an acrylonitrile-butadiene-acrylic acid copolymer, an acrylonitrile-butadiene-styrene copolymer, polyvinyl acetate, nylon and the like. These may be used singly or may be used in combination of two or more kinds. Among these, preferably used is at least one kind selected from the group consisting of a (meth)acrylic resin, a phenoxy resin and a polyimide resin.

[0077]

The weight average molecular weight of the film forming resin (D) is not particularly limited, but it is preferably equal to or more than 10,000, more preferably from 20,000 to 1,000,000 and further preferably from 30,000 to 900,000. When the weight average molecular weight is in the above range, film-forming properties of the adhesive film can be further improved.

[0078]

The content of the film forming resin (D) is not

particularly limited, but it is preferably from 5 to 70% by weight, more preferably from 10 to 60% by weight and particularly preferably from 15 to 55% by weight, based on the adhesive film. When the content is within the above
5 range, the fluidity of the adhesive film is suppressed and handling of the adhesive film is facilitated.

[0079]

The adhesive film of the present invention may further contain other components in addition to the aforementioned
10 components.

[0080]

(E) Curing Accelerator

The curing accelerator (E) may be properly selected depending on the kind of a curable resin or the like prior
15 to use. Examples of the curing accelerator (E) include trisubstituted phosphoniophenolate or a salt thereof, an imidazole compound having a melting point of equal to or more than 150 degrees centigrade and the like. From the viewpoint that the curability of the adhesive film may be
20 effectively improved with the addition of the curing accelerator in a small amount, preferably used is an imidazole compound having a melting point of equal to or more than 150 degrees centigrade. When the melting point of the aforementioned imidazole compound is equal to or
25 more than 150 degrees centigrade, the terminal of the adherend and the terminal of the support can be bonded to each other before completion of curing of the adhesive film.

Examples of the imidazole compound having a melting point of equal to or more than 150 degrees centigrade include 2-phenyl-4-methyl-5-hydroxymethylimidazole, 2-phenyl-4-methylimidazole and the like.

5 [0081]

The content of the curing accelerator (E) is not particularly limited, but it is preferably from 0.005 to 10% by weight and more preferably from 0.01 to 5% by weight, based on the adhesive film. When the mixing amount of the
10 imidazole compound is equal to or more than the above lower limit, the function as the curing accelerator (E) can be further effectively exhibited and the curability of the adhesive film can be improved. When the mixing amount of imidazole is equal to or less than the above upper limit,
15 the terminal of the adherend and the terminal of the support can be bonded to each other before completion of curing of the adhesive film, and storage stability of the adhesive film can be further improved. These curing accelerators (E) may be used singly or may be used in
20 combination of two or more kinds.

[0082]

(F) Silane Coupling Agent

The adhesive film may further contain a silane coupling agent (F). With the addition of the silane coupling agent
25 (F), adhesion of the adhesive film to the support or the adherend such as the semiconductor chip, the substrate or the like is increased. Examples of the silane coupling

agent (F) include an epoxysilane coupling agent, an aromatic-ring containing aminosilane coupling agent and the like. These may be used singly or may be used in combination of two or more kinds. The mixing amount of the silane coupling agent (F) may be properly selected, but it is preferably from 0.01 to 10% by weight, more preferably from 0.05 to 5% by weight and further preferably from 0.1 to 2% by weight, based on the adhesive film.

[0083]

10 (G) Filler

The adhesive film may further contain a filler (G). Thus, the linear expansion coefficient of the adhesive film is lowered and the minimum melt viscosity of the adhesive film is adjusted in the range of 0.01 to 10,000 Pa·s.

15 [0084]

Examples of the filler (G) include silver, titanium oxide, silica, mica and the like. However, among these, preferably used is silica. Examples of the shape of the silica filler include crushed silica, spherical silica and the like, and preferably used is spherical silica.

[0085]

The average particle diameter of the filler (G) is not particularly limited, but it is preferably equal to or more than 0.01 μm and equal to or less than 20 μm , and particularly preferably equal to or more than 0.1 μm and equal to or less than 5 μm . When it is in the above range, aggregation of the filler (G) in the adhesive film can be

suppressed and its appearance can be improved.

[0086]

The content of the filler (G) is not particularly limited, but it is preferably equal to or more than 0.1% by weight, more preferably equal to or more than 3% by weight, further preferably equal to or more than 5% by weight, and further more preferably equal to or more than 8% by weight, based on the adhesive film. On the other hand, it is preferably equal to or less than 80% by weight, more preferably equal to or less than 60% by weight and further preferably equal to or less than 55% by weight, based on the adhesive film. When the content of the filler is equal to or more than the above lower limit, the difference in linear expansion coefficients between the adhesive film after curing and adherends is reduced, and the stress generated during thermal shock is reduced, so that detachment of adherends can be further surely suppressed. On the other hand, when the content of the filler is equal to or less than the above upper limit, an excessive increase in the elastic modulus of the adhesive film after curing is suppressed, so that the reliability of the semiconductor device is improved. When the content of the filler is in the above range, the minimum melt viscosity of the adhesive film is easily adjusted to 0.01 to 10,000 Pa·s.

[0087]

The aforementioned respective resin components are

mixed to a solvent to give a varnish. The varnish is applied to a base material subjected to peeling of a polyester sheet or the like, and the resulting material is dried at a prescribed temperature until it is

5 substantially free from the solvent, whereby it is possible to obtain an adhesive film. The solvent used herein is not particularly limited as long as it is inert with respect to the components to be used. Suitably used are ketones such as acetone, methyl ethyl ketone, methyl

10 isobutyl ketone, DIBK (diisobutyl ketone), cyclohexanone, DAA (diacetone alcohol) and the like; aromatic hydrocarbons such as benzene, xylene, toluene and the like; alcohols such as methyl alcohol, ethyl alcohol, isopropyl alcohol, n-butyl alcohol and the like;

15 cellosolves such as methyl cellosolve, ethyl cellosolve, butyl cellosolve, methyl cellosolve acetate, ethyl cellosolve acetate and the like; NMP (N-methyl-2-pyrrolidone), THF (tetrahydrofuran), DMF (dimethylformamide), DBE (dibasic acid ester), EEP (ethyl

20 3-ethoxypropionate), DMC (dimethyl carbonate) and the like. As the amount of the solvent used, the solid content of the components mixed to the solvent is preferably in the range of 10 to 60% by weight.

[0088]

25 The thickness of the obtained adhesive film is not particularly limited, but it is preferably from 1 to 300 μm and particularly preferably from 5 to 200 μm . When the

thickness is within the above range, the resin components can be fully filled in the gap between bonding portions and the mechanical adhesion strength after curing of the resin components can be secured.

5 [0089]

The thus-obtained adhesive film has a flux activity. Accordingly, the adhesive film may be suitably used in connection of members requiring solder connection such as a semiconductor chip and a substrate, a substrate and a
10 substrate, a semiconductor chip and a semiconductor chip, a semiconductor wafer and a semiconductor wafer, and the like.

[0090]

Multilayer Circuit Board, Electronic Component,
15 Semiconductor Device

Next, the multilayer circuit board, the electronic component and the semiconductor device using the aforementioned adhesive film will be described.

[0091]

20 Fig. 1 is a process cross-sectional view illustrating one example of the method for producing a semiconductor device using the adhesive film of the present invention.

First, as shown in Fig. 1, a semiconductor chip 1 having solder bumps 11 is prepared (Fig. 1(a)).

25 [0092]

An adhesive film 2 having the aforementioned flux function is laminated to the semiconductor chip 1 so as

to cover the solder bumps 11 of the semiconductor chip 1 (Fig. 1(b)).

[0093]

As a method of laminating the adhesive film 2 having
5 the flux function to the semiconductor chip 1, there may be used, for example, a roll laminator, a flat-plate press, a wafer laminator and the like. Among these, preferably used is a method of laminating under vacuum (vacuum laminator) so as not to entrain air during lamination.

10 [0094]

The laminating conditions are not particularly limited as long as they may enable lamination without voids. However, specifically, the temperature is preferably from 60 to 150 degrees centigrade and the time is preferably
15 from 1 to 120 seconds, while the temperature is particularly preferably from 80 to 120 degrees centigrade and the time is particularly preferably from 5 to 60 seconds. When the laminating conditions are within the above range, the adhesive film is excellent in a balance
20 among adhesion, suppression of extrusion of the resin and the degree of cure of the resin.

[0095]

The pressurization condition is not particularly limited either, but it is preferably from 0.2 to 2.0 MPa
25 and particularly preferably from 0.5 to 1.5 MPa.

[0096]

Next, a substrate 3 having a pad portion (not

illustrated) on a position corresponding to the solder bumps 11 of the aforementioned semiconductor chip 1 is prepared, and the semiconductor chip 1 and the substrate 3 are temporarily compression-bonded through the adhesive film 2 having a flux function while aligning the semiconductor chip 1 with the substrate 3 (Fig. 1(c)). The temporary compression-bonding conditions are not particularly limited, but the temperature is preferably from 60 to 150 degrees centigrade and the time is preferably from 1 to 120 seconds, while the temperature is particularly preferably from 80 to 120 degrees centigrade and the time is particularly preferably from 5 to 60 seconds. In addition, the pressurization condition is not particularly limited either, but it is preferably from 0.2 to 2.0 MPa and particularly preferably from 0.5 to 1.5 MPa.

[0097]

Next, the solder bumps 11 are melted to form solder connection portions 111 for bonding the pad and the solders (Fig. 1(d)).

[0098]

The solder connecting condition also varies depending on the kind of the solders in use. For example, in case of Sn-3.5Ag, solders are preferably heated at a temperature of 220 to 260 degrees centigrade for 5 to 500 seconds and particularly preferably at 230 to 240 degrees centigrade for 10 to 100 seconds to carry out solder

connection.

[0099]

This solder bonding is preferably carried out under the conditions such that the solder bumps 11 are melted and solders are bonded to the pad, and then the adhesive film 2 is thermally cured. That is, the solder bonding is preferably carried out under the conditions such that the curing reaction of the adhesive film 2 does not much proceed although the solder bumps 11 are melted. Thus, the solder bumps 11 and the pad can be surely solder-bonded.

[0100]

Then, the adhesive film 2 is heated and cured. The curing conditions are not particularly limited, but the temperature is preferably from 130 to 220 degrees centigrade and the time is preferably from 30 to 500 minutes, while the temperature is particularly preferably from 150 to 200 degrees centigrade and the time is particularly preferably from 60 to 180 minutes.

[0101]

In this manner, it is possible to obtain a semiconductor device 10 in which the semiconductor chip 1 and the substrate 3 are attached to each other with a cured product of the adhesive film 2. The semiconductor device 10 is excellent in the electrical connection reliability since the cured product of the adhesive film 2 is used for attachment as described above. Furthermore, by the use

of the adhesive film 2, the solder bumps 11 and the pad are surely solder-bonded and at the same time the gaps due to solder bonding are encapsulated, thus achieving high productivity.

5 [0102]

Furthermore, a circuit board and a circuit board are bonded to each other with the cured product of the adhesive film 2 according to the same method, whereby it is possible to obtain a multilayer circuit board.

10 [0103]

Also, a semiconductor chip and a semiconductor chip are bonded to each other with the cured product of the adhesive film 2 according to the same method, whereby it is possible to obtain an electronic component.

15 [0104]

Hereinafter, the present invention will be described in detail by way of Examples and Comparative Examples. However, the present invention is not restricted to these Examples and Comparative Examples.

20

EXAMPLES

[0105]

Example 1

Preparation of Varnish for Adhesive Film

25 55.0 weight parts of a bisphenol F type epoxy resin (EPICLON-830LVP, commercially available from DIC Corporation) as the thermosetting resin (A), 30.8 weight

parts of a phenol novolac resin (VR-9305, commercially available from Mitsui Chemicals, Inc.) as the curing agent (B), 3.0 weight parts of sebacic acid (a product of Tokyo Chemical Industry, Co., Ltd.) as the compound having flux activity (C), 10.0 weight parts of a bisphenol F type phenoxy resin (YP-70, commercially available from Tohto Kasei Co., Ltd.) as the film forming resin (D), 0.2 weight parts of 2-phenyl-4-methylimidazole (2P4MZ, commercially available from Shikoku Chemicals Corp.) as the curing accelerator (E), and 1.0 weight part of β -(3,4-epoxycyclohexyl)ethyltrimethoxysilane (KBM-303, commercially available from Shin-Etsu Chemical Co., Ltd.) as the silane coupling agent (F) were dissolved in methyl ethyl ketone, whereby a resin varnish having a resin concentration of 50% was prepared.

[0106]

Preparation of Adhesive Film

The resulting resin varnish was applied on a base material polyester film (Lumira, commercially available from Toray Co., Ltd.) so as to have a thickness of 50 μm , and the resulting material was dried at 100 degrees centigrade for 5 minutes to obtain an adhesive film having a thickness of 25 μm .

[0107]

Preparation of Semiconductor Device

The resulting adhesive film was laminated to a semiconductor chip (size: 10 mm $\times$ 10 mm, thickness: 0.3

mm) having solder bumps (Sn-3.5Ag, melting point: 221 degrees centigrade) at 100 degrees centigrade with a vacuum roll laminator, whereby an adhesive film-attached semiconductor chip was obtained.

5 Then, while aligning a pad portion of a circuit board having a pad portion with a gold-plated surface and the solder bumps to come into contact with each other, the semiconductor chip was temporarily compression-bonded to the circuit board at 100 degrees centigrade for 30 seconds
10 using a flip chip bonder (a product of Shibuya Kogyo Co., Ltd.).

Next, the resulting material was heated at 235 degrees centigrade for 30 seconds using a flip chip bonder (a product of Shibuya Kogyo Co., Ltd.), whereby solder bumps
15 were melted to carry out solder connection.

Furthermore, the adhesive film was cured by heating at 180 degrees centigrade for 60 minutes, whereby a semiconductor device in which the semiconductor chip and the circuit board were attached with the cured product of
20 the adhesive film was obtained.

[0108]

Example 2

Preparation of Varnish for Adhesive Film

An adhesive film and a semiconductor device were
25 prepared in the same manner as in Example 1, except that 50.0 weight parts of a bisphenol A type epoxy resin (EPICLON-840S, commercially available from DIC

Corporation) as the thermosetting resin (A), 25.5 weight parts of a phenol novolac resin (VR-9305, commercially available from Mitsui Chemicals, Inc.) as the curing agent (B), 3.0 weight parts of sebacic acid (a product of Tokyo Chemical Industry, Co., Ltd.) as the compound having flux activity (C), 20.0 weight parts of a bisphenol F type phenoxy resin (YP-70, commercially available from Tohto Kasei Co., Ltd.) as the film forming resin (D), 0.5 weight parts of 2-phenyl-4-methylimidazole (2P4MZ, commercially available from Shikoku Chemicals Corp.) as the curing accelerator (E), and 1.0 weight part of β -(3,4-epoxycyclohexyl)ethyltrimethoxysilane (KBM-303, commercially available from Shin-Etsu Chemical Co., Ltd.) as the silane coupling agent (F) were dissolved in methyl ethyl ketone to prepare a resin varnish having a resin concentration of 50%.

[0109]

Example 3

Preparation of Varnish for Adhesive Film

20 An adhesive film and a semiconductor device were prepared in the same manner as in Example 1, except that 20.0 weight parts of a cresol novolac type epoxy resin (EOCN-1020-70, commercially available from Nippon Kayaku Co., Ltd.) as the thermosetting resin (A), 15.0 weight parts of a phenol novolac resin (PR55617, commercially available from Sumitomo Bakelite Co., Ltd.) as the curing agent (B), 3.0 weight parts of sebacic acid (a product of

Tokyo Chemical Industry, Co., Ltd.) as the compound having flux activity (C), 60.0 weight parts of a bisphenol A type phenoxy resin (YP-50, commercially available from Tohto Kasei Chemical Co., Ltd.) as the film forming resin (D),
5 1.0 weight part of 2-phenyl-4-methylimidazole (2P4MZ, commercially available from Shikoku Chemicals Corp.) as the curing accelerator (E), and 1.0 weight part of β -(3,4-epoxycyclohexyl)ethyltrimethoxysilane (KBM-303, commercially available from Shin-Etsu Chemical Co., Ltd.)
10 as the silane coupling agent (F) were dissolved in methyl ethyl ketone to prepare a resin varnish having a resin concentration of 50%.

[0110]

Example 4

15 Preparation of Varnish for Adhesive Film

An adhesive film and a semiconductor device were prepared in the same manner as in Example 1, except that
15.0 weight parts of a cresol novolac type epoxy resin (EOCN-1020-70, commercially available from Nippon Kayaku
20 Co., Ltd.) as the thermosetting resin (A), 8.0 weight parts of a phenol novolac resin (PR55617, commercially available from Sumitomo Bakelite Co., Ltd.) as the curing agent (B), 6.0 weight parts of phenolphthalin (a product of Tokyo Chemical Industry, Co., Ltd.) as the compound having flux
25 activity (C), 46.0 weight parts of a bisphenol A type phenoxy resin (YP-50, commercially available from Tohto Kasei Co., Ltd.) as the film forming resin (D), 23.0 weight

parts of a spherical silica filler (SE6050, commercially available from Admatechs Co., Ltd., average particle diameter: 2 μ m) as the filler (G), 1.0 weight part of 2-phenyl-4-methylimidazole (2P4MZ, commercially available from Shikoku Chemicals Corp.) as the curing accelerator (E), and 1.0 weight part of β -(3,4-epoxycyclohexyl)ethyltrimethoxysilane (KBM-303, commercially available from Shin-Etsu Chemical Co., Ltd.) as the silane coupling agent (F) were dissolved in methyl ethyl ketone to prepare a resin varnish having a solid content concentration of 40%.

[0111]

Example 5

Preparation of Varnish for Adhesive Film

15 An adhesive film and a semiconductor device were prepared in the same manner as in Example 1, except that 13.0 weight parts of a cresol novolac type epoxy resin (EOCN-1020-70, commercially available from Nippon Kayaku Co., Ltd.) as the thermosetting resin (A), 6.0 weight parts
20 of a phenol novolac resin (PR55617, commercially available from Sumitomo Bakelite Co., Ltd.) as the curing agent (B), 5.0 weight parts of phenolphthalin (a product of Tokyo Chemical Industry, Co., Ltd.) as the compound having flux activity (C), 39.0 weight parts of a bisphenol A type
25 phenoxy resin (YP-50, commercially available from Tohto Kasei Co., Ltd.) as the film forming resin (D), 36.0 weight parts of a spherical silica filler (SE6050, commercially

available from Admatechs Co., Ltd., average particle diameter: 2 μ m) as the filler (G), 0.5 weight parts of 2-phenyl-4-methylimidazole (2P4MZ, commercially available from Shikoku Chemicals Corp.) as the curing
5 accelerator (E), and 0.5 weight parts of β -(3,4-epoxycyclohexyl)ethyltrimethoxysilane (KBM-303, commercially available from Shin-Etsu Chemical Co., Ltd.) as the silane coupling agent (F) were dissolved in methyl ethyl ketone to prepare a resin varnish having a solid
10 content concentration of 30%.

[0112]

Example 6

Preparation of Varnish for Adhesive Film

An adhesive film and a semiconductor device were
15 prepared in the same manner as in Example 1, except that 9.0 weight parts of a cresol novolac type epoxy resin (EOCN-1020-70, commercially available from Nippon Kayaku Co., Ltd.) as the thermosetting resin (A), 4.0 weight parts of a phenol novolac resin (PR55617, commercially available
20 from Sumitomo Bakelite Co., Ltd.) as the curing agent (B), 4.0 weight parts of phenolphthalin (a product of Tokyo Chemical Industry, Co., Ltd.) as the compound having flux activity (C), 27.0 weight parts of an acrylic acid ester copolymer resin (SG-P3, commercially available from
25 Nagase Chemtex Corp.) as the film forming resin (D), 55.0 weight parts of a spherical silica filler (SE6050, commercially available from Admatechs Co., Ltd., average

particle diameter: 2 μ m) as the filler (G), 0.5 weight parts of 2-phenyl-4-methylimidazole (2P4MZ, commercially available from Shikoku Chemicals Corp.) as the curing accelerator (E), and 0.5 weight parts of

5 β -(3,4-epoxycyclohexyl)ethyltrimethoxysilane (KBM-303, commercially available from Shin-Etsu Chemical Co., Ltd.) as the silane coupling agent (F) were dissolved in methyl ethyl ketone to prepare a resin varnish having a solid content concentration of 20%.

10 [0113]

Example 7

Preparation of Varnish for Adhesive Film

An adhesive film and a semiconductor device were prepared in the same manner as in Example 1, except that

15 55.0 weight parts of a bisphenol F type epoxy resin (EPICLON-830LVP, commercially available from DIC

Corporation) as the thermosetting resin (A), 31.8 weight parts of a phenol novolac resin (VR-9305, commercially available from Mitsui Chemicals, Inc.) as the curing agent

20 (B), 2.0 weight parts of sebacic acid (a product of Tokyo Chemical Industry, Co., Ltd.) as the compound having flux activity (C), 10.0 weight parts of a bisphenol F type

phenoxy resin (YP-70, commercially available from Tohto Kasei Co., Ltd.) as the film forming resin (D), 0.2 weight

25 parts of 2-phenyl-4-methylimidazole (2P4MZ, commercially available from Shikoku Chemicals Corp.) as the curing accelerator (E), and 1.0 weight part of

β -(3,4-epoxycyclohexyl)ethyltrimethoxysilane (KBM-303, commercially available from Shin-Etsu Chemical Co., Ltd.) as the silane coupling agent (F) were dissolved in methyl ethyl ketone to prepare a resin varnish having a resin
5 concentration of 50%.

[0114]

Example 8

Preparation of Varnish for Adhesive Film

An adhesive film and a semiconductor device were
10 prepared in the same manner as in Example 1, except that 15.0 weight parts of a cresol novolac type epoxy resin (EOCN-1020-70, commercially available from Nippon Kayaku Co., Ltd.) as the thermosetting resin (A), 5.0 weight parts of a phenol novolac resin (VR-9305, commercially available
15 from Mitsui Chemicals, Inc.) as the curing agent (B), 60.0 weight parts of sebacic acid (a product of Tokyo Chemical Industry, Co., Ltd.) as the compound having flux activity (C), 18.0 weight parts of a bisphenol A type phenoxy resin (YP-50, commercially available from Tohto Kasei Co., Ltd.)
20 as the film forming resin (D), 1.0 weight part of 2-phenyl-4-methylimidazole (2P4MZ, commercially available from Shikoku Chemicals Corp.) as the curing accelerator (E), and 1.0 weight part of
25 β -(3,4-epoxycyclohexyl)ethyltrimethoxysilane (KBM-303, commercially available from Shin-Etsu Chemical Co., Ltd.) as the silane coupling agent (F) were dissolved in methyl ethyl ketone to prepare a resin varnish having a resin

concentration of 50%.

[0115]

Comparative Example 1

Preparation of Varnish for Adhesive Film

5 An adhesive film and a semiconductor device were prepared in the same manner as in Example 1, except that 59.0 weight parts of a bisphenol F type epoxy resin (EPICLON-830LVP, commercially available from DIC Corporation) as the thermosetting resin (A), 34.9 weight
10 parts of a phenol novolac resin (VR-9305, commercially available from Mitsui Chemicals, Inc.) as the curing agent (B), 3.0 weight parts of sebacic acid (a product of Tokyo Chemical Industry, Co., Ltd.) as the compound having flux activity (C), 2.0 weight parts of a bisphenol F type
15 phenoxy resin (YP-70, commercially available from Tohto Kasei Co., Ltd.) as the film forming resin (D), 0.1 weight part of 2-phenyl-4-methylimidazole (2P4MZ, commercially available from Shikoku Chemicals Corp.) as the curing accelerator (E), and 1.0 weight part of
20 β -(3,4-epoxycyclohexyl)ethyltrimethoxysilane (KBM-303, commercially available from Shin-Etsu Chemical Co., Ltd.) as the silane coupling agent (F) were dissolved in methyl ethyl ketone to prepare a resin varnish having a resin concentration of 50%.

25 [0116]

Comparative Example 2

Preparation of Varnish for Adhesive Film

An adhesive film and a semiconductor device were prepared in the same manner as in Example 1, except that 20.0 weight parts of a cresol novolac type epoxy resin (EOCN-1020-70, commercially available from Nippon Kayaku Co., Ltd.) as the thermosetting resin (A), 10.0 weight parts of a phenol novolac resin (PR55167, commercially available from Sumitomo Bakelite Co., Ltd.) as the curing agent (B), 8.0 weight parts of phenolphthalin (a product of Tokyo Chemical Industry, Co., Ltd.) as the compound having flux activity (C), 60.0 weight parts of an acrylic acid ester copolymer resin (SG-P3, commercially available from Tohto Kasei Co., Ltd.) as the film forming resin (D), 1.0 weight part of 2-phenyl-4-methylimidazole (2P4MZ, commercially available from Shikoku Chemicals Corp.) as the curing accelerator (E), 1.0 weight part of β -(3,4-epoxycyclohexyl)ethyltrimethoxysilane (KBM-303, commercially available from Shin-Etsu Chemical Co., Ltd.) as the silane coupling agent (F), and 300.0 weight parts of a spherical silica filler (SE6050, commercially available from Admatechs Co., Ltd., average particle diameter: 2 μ m) as the filler (G) were dissolved in methyl ethyl ketone to prepare a resin varnish having a resin concentration of 50%.

[0117]

25 Comparative Example 3

Preparation of Varnish for Adhesive Film

An adhesive film and a semiconductor device were

prepared in the same manner as in Example 1, except that 42.0 weight parts of a bisphenol F type epoxy resin (EPICLON-830LVP, commercially available from DIC Corporation) as the thermosetting resin (A), 30.0 weight parts of a phenol novolac resin (VR-9305, commercially available from Mitsui Chemicals, Inc.) as the curing agent (B), 3.0 weight parts of sebacic acid (a product of Tokyo Chemical Industry, Co., Ltd.) as the compound having flux activity (C), 15.0 weight parts of an acrylic acid ester copolymer resin (SG-P3, commercially available from Tohto Kasei Co., Ltd.) as the film forming resin (D), 0.01 weight part of 2-phenyl-4-methylimidazole (2P4MZ, commercially available from Shikoku Chemicals Corp.) as the curing accelerator (E), and 10.0 weight parts of β -(3,4-epoxycyclohexyl)ethyltrimethoxysilane (KBM-303, commercially available from Shin-Etsu Chemical Co., Ltd.) as the silane coupling agent (F) were dissolved in methyl ethyl ketone to prepare a resin varnish having a resin concentration of 50%.

[0118]

Meanwhile, the adhesive films and the semiconductor devices obtained in the respective Examples and Comparative Examples were evaluated in the following manner. Evaluation items are also shown along with a description of each item. The obtained results are shown in Table 1.

[0119]

1. Minimum Melt Viscosity of Adhesive Film

The melt viscosities of the resulting adhesive films in the respective Examples and Comparative Examples were measured under the conditions of a parallel plate of 20 mmφ, a gap of 0.05 mm, a frequency of 0.1 Hz and a temperature increase rate of 10 degrees centigrade/min using a viscoelasticity measuring instrument (RheoStress RS150, commercially available from HAKKE Corp.). The lowest melt viscosity was taken as the measured value.

[0120]

2. 5% weight loss temperature by thermogravimetry (b) - Exothermic Peak Temperature (a) of Adhesive Film

For the exothermic peak temperature (a) of the adhesive films obtained in the respective Examples and Comparative Examples, the curing heat value was measured under the condition of a temperature increase rate of 10 degrees centigrade/min using a differential scanning calorimeter (DSC-6200, commercially available from Seiko Instruments Inc.). The peak temperature (degrees centigrade) was taken as the measured value.

Subsequently, for the 5% weight loss temperature by thermogravimetry (b) of the resulting adhesive films in the respective Examples and Comparative Examples, the weight loss on heating was measured under the condition of a temperature increase rate of 10 degrees centigrade/min using a thermo-gravimetric/differential thermal analyzer (TG/DTA6200, commercially available from

Seiko Instruments Inc.). The 5% weight loss temperature (degrees centigrade) was taken as the measured value.

(b)-(a) was calculated from the resulting (a) and (b).

[0121]

5 3. Cavities and Voids in Semiconductor Device

With respect to every twenty semiconductor devices obtained in the respective Examples and Comparative Examples, cavities and voids (bubbles) were evaluated by carrying out cross-sectional observation of the solder
10 bumps of the semiconductor chip and the pad portion of the circuit board according to SEM (scanning electron microscope). Respective symbols are as follows.

o: Cavities and voids of equal to or more than 5 μm were not observed.

15 *: Cavities and voids of equal to or more than 5 μm were observed.

[0122]

4. Electrical Connectivity of Semiconductor Device

With respect to every twenty semiconductor devices
20 obtained in the respective Examples and Comparative Examples, connection resistance between the semiconductor chip and the circuit board was measured with a digital multimeter respectively at 10 points to evaluate connection reliability. Respective symbols are as
25 follows.

o: Connection resistances of all twenty semiconductor devices (measurement points: $20 \times 10 = 200$) were equal to or

less than 3Ω .

Δ : Although all points were electrically connected, connection resistances of 10 to 20 points were equal to or more than 3Ω (practically no problem caused).

5 $\times$: Connection resistances of equal to or more than 20 points were equal to or more than 3Ω , and open defect was detected at equal to or more than 1 point (practical problem caused).

[0123]

10 5. Insulation Reliability of Semiconductor Device

With respect to every twenty semiconductor devices obtained in the respective Examples and Comparative Examples, while applying a voltage of 3V under an environment of a temperature of 130 degrees centigrade and
15 a relative humidity of 85%RH, insulation resistances between adjacent bumps were respectively measured in a continuous manner at 3 points (200 hr) to evaluate ionic migration. Respective symbols are as follows.

o: In all measurement points ($20 \times 3 = 60$), dielectric
20 breakdown was not caused.

Δ : Dielectric breakdown was caused in less than 3 points.

$\times$: Dielectric breakdown was caused in equal to or more than 3 points.

25 [0124]

[Table 1]

		Component	Example 1	Example 2	Example 3	Example 4	Example 5	Example 6
Mixing	(A) Thermosetting resin	(A-1)	55.0					
		(A-2)		50.0				
		(A-3)			20.0	15.0	13.0	9.0
	(B) Curing agent	(B-1)	30.8	25.5				
		(B-2)			15.0	8.0	6.0	4.0
	(C) Compound having flux activity	(C-1)	3.0	3.0	3.0			
		(C-2)				6.0	5.0	4.0
	(D) Film forming agent	(D-1)	10.0	20.0				
		(D-2)			60.0	46.0	39.0	
		(D-3)						27.0
	(E) Curing accelerator	(E-1)	0.2	0.5	1.0	1.0	0.5	0.5
	(F) Silane coupling agent	(F-1)	1.0	1.0	1.0	1.0	0.5	0.5
Evaluation	(G) Filler	(G-1)				23.0	36.0	55.0
	Total amount of resin composition		100.0	100.0	100.0	100.0	100.0	100.0
	(A)/(C)		18.3	16.7	6.7	2.5	2.6	2.3
	Minimum melt viscosity [Pa·s]		0.02	5	60	300	1800	7000
	Exothermic peak temperature (a) [degrees centigrade]		218	195	188	194	200	203
	5% weight loss temperature by thermogravimetry (b) [degrees centigrade]		386	394	399	401	401	403
	(b)-(a)		168	199	211	207	201	200
	Cavities/Voids		o	o	o	o	o	o
	Electrical connectivity		o	o	o	o	o	o
	Insulation reliability (migration)		o	o	o	o	o	o

[Table 1 (continued)]

		Component	Example 7	Example 8	Comparative Example 1	Comparative Example 2	Comparative Example 3
Mixing	(A) Thermosetting resin	(A-1)	55.0		59.0		42.0
		(A-2)					
		(A-3)		15.0		20.0	
	(B) Curing agent	(B-1)	31.8	5.0	34.9		30.0
		(B-2)				10.0	
	(C) Compound having flux activity	(C-1)	2.0	60.0	3.0		3.0
		(C-2)				8.0	
	(D) Film forming agent	(D-1)	10.0		2.0		
		(D-2)		18.0			
		(D-3)				60.0	15.0
	(E) Curing accelerator	(E-1)	0.2	1.0	0.1	1.0	0.01
	(F) Silane coupling agent	(F-1)	1.0	1.0	1.0	1.0	10.0
Evaluation	(G) Filler	(G-1)				300.0	
	Total amount of resin composition		100.0	100.0	100.0	100.0	100.0
	(A)/(C)		27.5	0.3	19.7	2.5	14.0
	Minimum melt viscosity [Pa·s]		0.05	5	0.005	14000	200
	Exothermic peak temperature (a) [degrees centigrade]		216	187	223	209	233
	5% weight loss temperature by thermogravimetry (b) [degrees centigrade]		387	392	379	405	331
	(b)-(a)		171	205	156	196	98
	Cavities/Voids		o	o	x	o	x
	Electrical connectivity		Δ	o	o	x	o
	Insulation reliability (migration)		o	Δ	o	o	o

[0125]

The respective components in the Table are described below.

5 (A-1) Bisphenol F type epoxy resin (model number: EPICLON-830LVP, commercially available from DIC Corp.)

(A-2) Bisphenol A type epoxy resin (model number: EPICLON-840S, commercially available from DIC Corp.)

(A-3) Cresol novolac type epoxy resin (model number: 10 EOCN-1020-70, commercially available from Nippon Kayaku Co., Ltd.)

(B-1) Phenol novolac resin (model number: VR-9305, commercially available from Mitsui Chemicals, Inc.)

(B-2) Phenol novolac resin (model number: PR55617, commercially available from Sumitomo Bakelite Co., Ltd.)

(C-1) Sebacic acid (a product of Tokyo Chemical Industry, Co., Ltd.)

5 (C-2) Phenolphthalin (a product of Tokyo Chemical Industry, Co., Ltd.)

(D-1) Bisphenol F type phenoxy resin (model number: YP-70, commercially available from Tohto Kasei Co., Ltd.)

10 (D-2) Bisphenol A type phenoxy resin (model number: YP-50, commercially available from Tohto Kasei Co., Ltd.)

(D-3) Acrylic acid ester copolymer resin (model number: SG-P3, commercially available from Nagase Chemtex Corp.)

(E-1) 2-phenyl-4-methylimidazole (model number: 2P4MZ, commercially available from Shikoku Chemicals Corp.)

15 (F-1) β -(3,4-epoxycyclohexyl)ethyltrimethoxysilane (model number: KBM-303, commercially available from Shin-Etsu Chemical Co., Ltd.)

(G-1) Spherical silica filler (model number: SE6050, commercially available from Admatechs Co., Ltd., average
20 particle diameter: 2 μ m)

[0126]

For the adhesive film obtained in Example 1, the minimum melt viscosity was 0.02 Pa·s, and the difference between the 5% weight loss temperature by thermogravimetry (b) and
25 the exothermic peak temperature (a) was 168 degrees centigrade. The semiconductor device was prepared with the adhesive film obtained in Example 1 and evaluated, and

as a result, all of cavities, voids, electrical connectivity and insulation reliability were excellent as shown in Table 1.

[0127]

5 Furthermore, the adhesive films and the semiconductor devices obtained in the respective Examples 2 to 8 exhibited almost the same behavior as those of Example 1.

[0128]

10 This application is based on Japanese patent application No. 2009-214528 filed on September 16, 2009, the content of which is incorporated hereinto by reference.

CLAIMS

1. An adhesive film electrically connecting a first terminal of a support and a second terminal of an adherend using solders, and attaching the support to the adherend, wherein the adhesive film comprises a thermosetting resin (A), a curing agent (B), a compound having flux activity (C) and a film forming resin (D), the minimum melt viscosity of the adhesive film is from 0.01 to 10,000 Pa·s, and the adhesive film satisfies the following formula (1) when the exothermic peak temperature (degrees centigrade) of the adhesive film is defined as (a) and the 5% weight loss temperature by thermogravimetry (degrees centigrade) of the adhesive film is defined as (b),
$$(b) - (a) \geq 100 \text{ degrees centigrade} \quad (1).$$

2. The adhesive film according to claim 1, wherein the mixing ratio ((A)/(C)) of the thermosetting resin (A) to the compound having flux activity (C) is from 0.5 to 20.

3. The adhesive film according to claim 1 or 2, wherein the content of the thermosetting resin (A) is from 5 to 80% by weight, based on said adhesive film.

4. The adhesive film according to any one of claims 1 to 3, wherein the thermosetting resin (A) is an epoxy resin.

5. The adhesive film according to any one of claims 1 to 4, wherein the compound having flux activity (C) is a flux activating compound having a carboxyl group and/or a phenolic hydroxyl group.

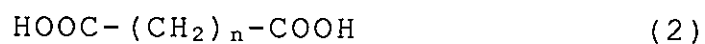
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6. The adhesive film according to any one of claims 1 to 4, wherein the compound having flux activity (C) is a flux activating compound containing, in one molecule thereof, two phenolic hydroxyl groups and at least one carboxyl group which is directly bonded to an aromatic ring.

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7. The adhesive film according to any one of claims 1 to 6, wherein the compound having flux activity (C) contains a compound represented by the following general formula

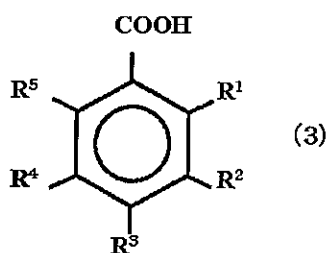
15 (2),



wherein, in the general formula (2), n is an integer of 1 to 20.

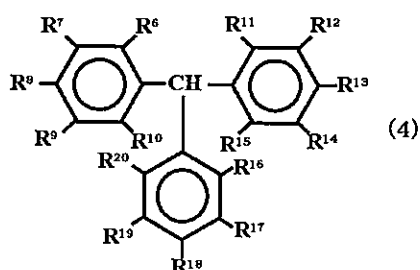
20 8. The adhesive film according to any one of claims 1 to 6, wherein the compound having flux activity (C) contains a compound represented by the following general formula (3) and/or (4),

[Chemical Formula (5)]



wherein, in the general formula (3), R^1 to R^5 are each independently a monovalent organic group, and at least one of R^1 to R^5 is a hydroxyl group,

5 [Chemical Formula (6)]



wherein, in the general formula (4), R^6 to R^{20} are each independently a monovalent organic group, and at least one of R^6 to R^{20} is a hydroxyl group or a carboxyl group.

10

9. The adhesive film according to any one of claims 1 to 8, wherein said adhesive film further contains a filler (G).

15 10. The adhesive film according to claim 9, wherein the content of the filler (G) is equal to or more than 0.1% by weight and equal to or less than 80% by weight, based on said adhesive film.

20 11. The adhesive film according to any one of claims 1 to

10, wherein said adhesive film further contains a silane coupling agent (F) in an amount of equal to or more than 0.01% by weight and equal to or less than 5% by weight, based on said adhesive film.

5

12. A multilayer circuit board, comprising a cured product of the adhesive film according to any one of claims 1 to 11.

10 13. An electronic component, comprising a cured product of the adhesive film according to any one of claims 1 to 11.

14. A semiconductor device, comprising a cured product of
15 the adhesive film according to any one of claims 1 to 11.